

(b) Amendments to the Claims

Please cancel claim 8. Please amend claims 1 and 5 as follows. A detailed listing of all the claims that are or were on the application is provided.

--1. (Currently Amended) Process for decomposing powdery by-product and residual non-reacted gas comprising silicon or a compound thereof as a main component formed during processing a silicon-based amorphous or microcrystalline substrate or film comprising:

(a) during processing the substrate or the film exhausting the unreacted gas and the powdery by-product{[,]} into a trap means having therein a filament comprising a high-melting metal material comprising as a main component at least one of tungsten, molybdenum or rhenium, said filament having a configuration comprising a single linear shape, a plurality of linear shapes or a linear shape spirally wound; and

(b) decomposing the non-reacted gas and the powdery by-product by heating to a temperature from 1400°C to 2200°C, whereby adherence of the powdery by-product to the trap means is reduced without compromising the integrity of the filament and vacuum seals around the trap.

2. (Previously Presented) The process according to claim 1, wherein a deposited film is formed on the substrate by a plasma CVD process.

3. (Previously Presented) The process according to claim 1, wherein a deposited film is formed on the substrate by a thermal CVD process.

4. (Previously Presented) The process according to claim 1, wherein a deposited film is formed on the substrate by a photo CVD process.

5. (Currently Amended) The process according to claim 1, wherein the film is processed by a dry etching process.

6.-10. (Cancelled)

11. (Previously Presented) The process according to claim 1, wherein a wall surface of the trap is of a double structure, and an inner wall surface is detachable.

12.-56. (Cancelled)